

Abstract of the Disclosure

An object of the present invention is to stably supply a treatment chamber with a treatment gas with a
5 prescribed composition. A spin on dielectric (SOD) system includes a film treatment apparatus of the present invention which comprises, for forming an interlayer insulating film, a treatment chamber for placing a wafer W, a first mass flow controller for NH₃ gas, a second mass flow controller for N₂ gas with a
10 prescribed water vapor, thereby supplying the treatment chamber with a gas of a prescribed composition.